

Radiation Failures in Intel 14nm Microprocessors

Dobrin P. Bossev¹, Adam R. Duncan¹, Matthew J. Gadlage¹, Austin H. Roach¹, Matthew J. Kay¹, Carl Szabo², Tammy J. Berger¹, Darin A. York¹, Aaron Williams¹, K. LaBel³ and James D. Ingalls¹

¹*NSWC Crane*, ²*AS&D*, ³*NASA GSFC*

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Agenda

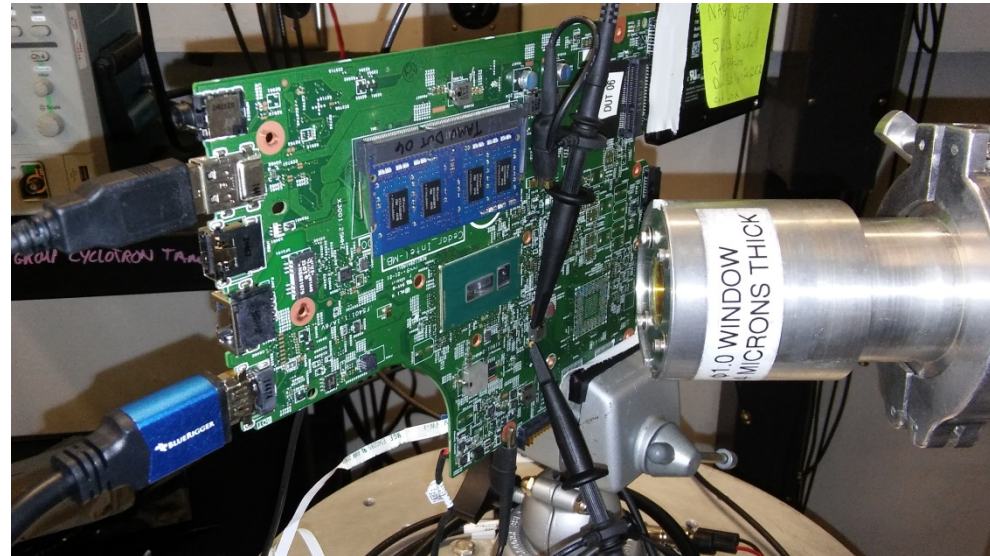
- Introduction & Motivation
- Soft & Hard Failures in FinFET processors
- Catastrophic Failures in 14nm node – Failure Analysis
 - Electrical Testing
 - Magnetic Microscopy
 - Photoemission Microscopy (PEM)
 - Laser Scanning Microscopy (LSM)
- Conclusions

Rad effects in microprocessors

- Microprocessors are too complex to be used for fundamental studies – too many blocks and circuits, too many processes
- Proprietary architecture
- Need to be investigated in their natural working environment

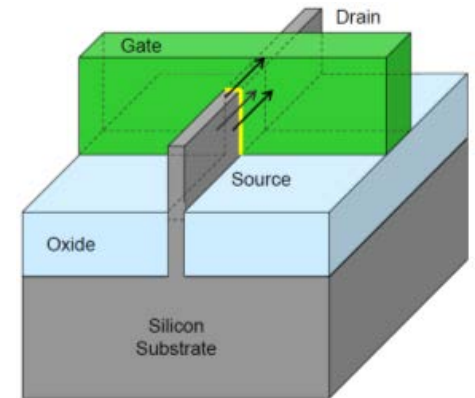
In this study:

- 14 nm Intel “Broadwell” 5th generation core series 5005U-i3 and 5200U-i5
- Mounted on Dell Inspiron laptops, MSI Cubi and Gigabyte Brix barebones
- Tested with Windows 8 and CentOS7 at idle



Rad studies are important as microprocessors are being flown in space ...

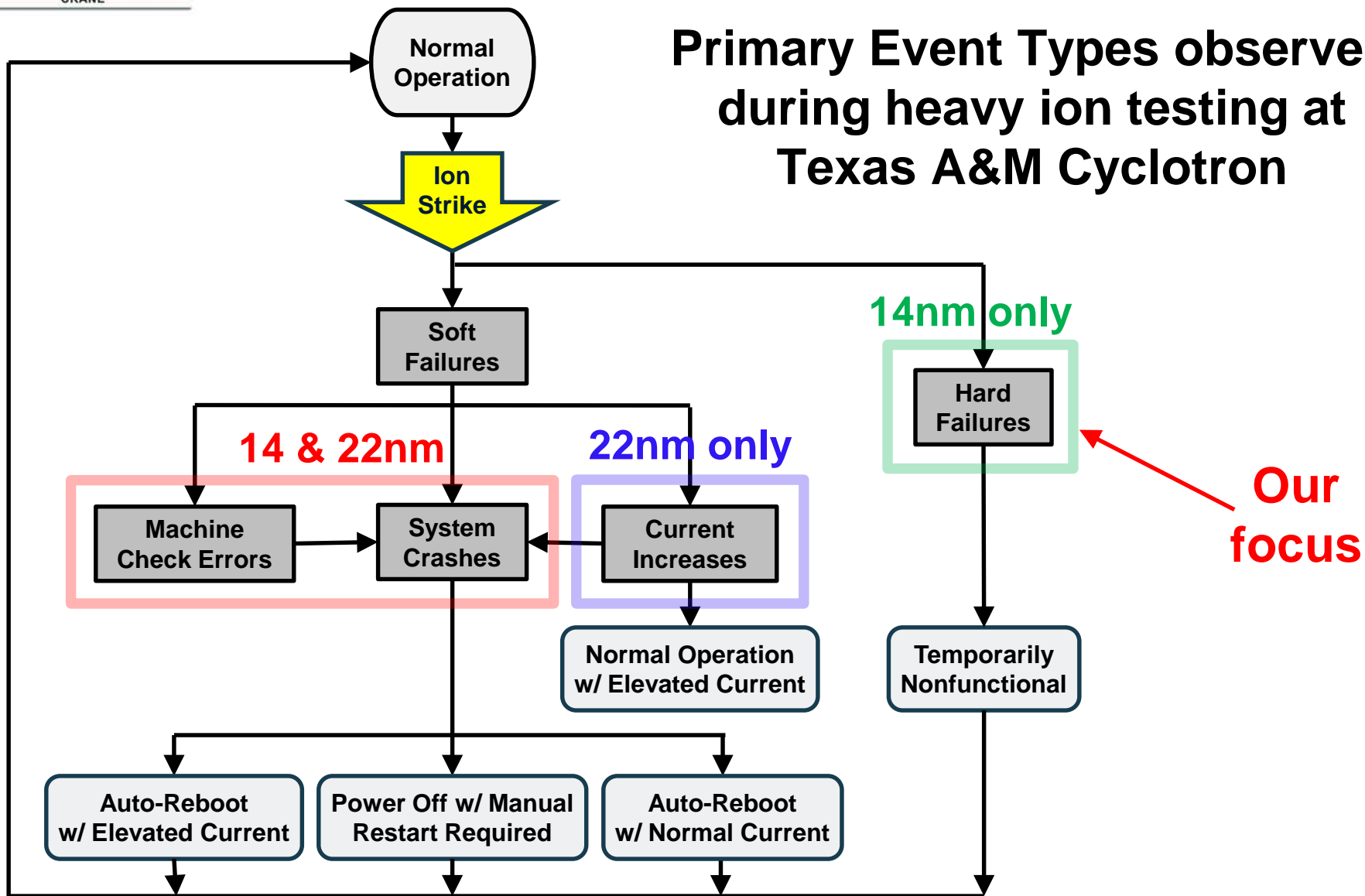
Introduction



- Intel 14 nm
 - New – 2012 (transistor in 2002)
 - Fabricated in bulk FinFET process (Tri-Gate)
 - Excellent performance vs power specifications
 - Spacecraft candidate electronics
- Previously published Intel Tri-Gate radiation effects data promising
 - **TID:** functional up to 4Mrad [Szabo 2015]
 - **Soft error rate:** 1.4x to 23x reduction compared to 32nm planar [Seifert 2014, 2015]
- Can you use FinFETs in space radiation environments?
 - Are there critical issues or showstoppers?
 - Limited FY16 FinFET commercial devices available
 - Intel microprocessors, proprietary cell phone ASICs

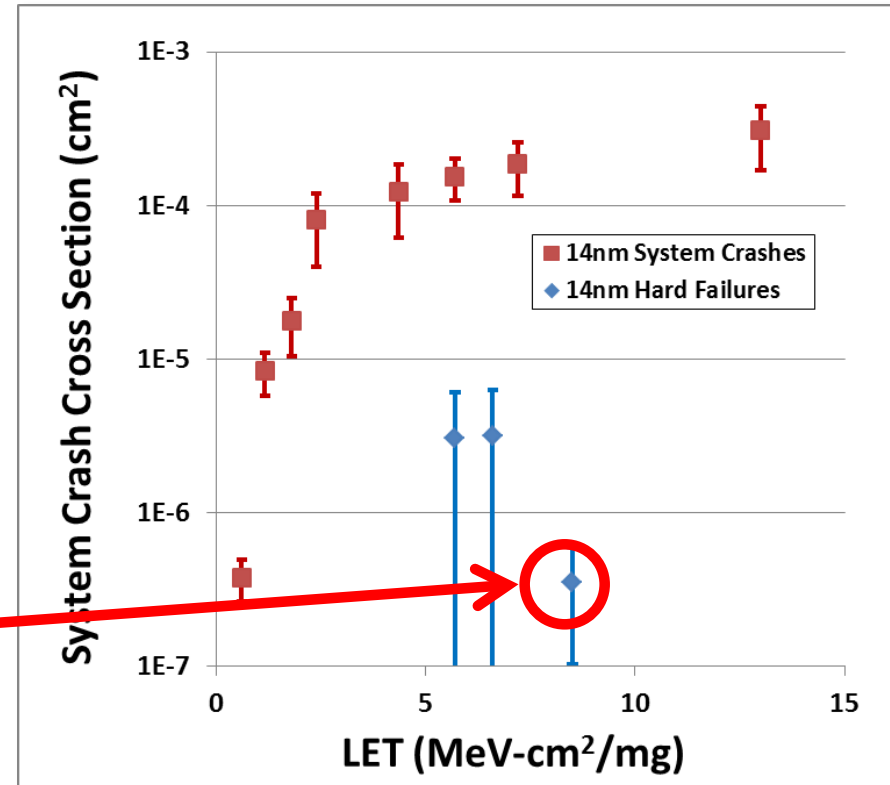
Observations *prior* to this study

Primary Event Types observed during heavy ion testing at Texas A&M Cyclotron



Hard Failures” in 14nm FinFET devices

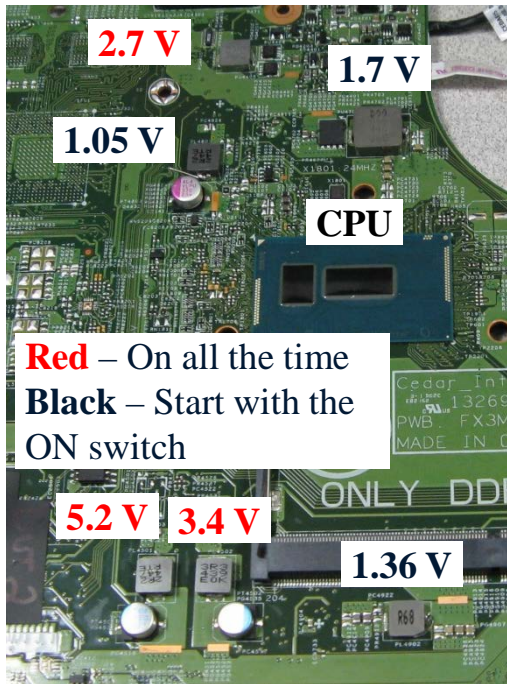
- System crash observed followed by inability to boot system for 30 min to hours
- Observed at 45° angles of incidence
- Occurs less often than system crashes. Very limited statistics – only 4 events
- **System crash observed followed by *permanent inability to boot*. A single event observed**



Understanding hard failure root cause is critical to future FinFET use in radiation environments

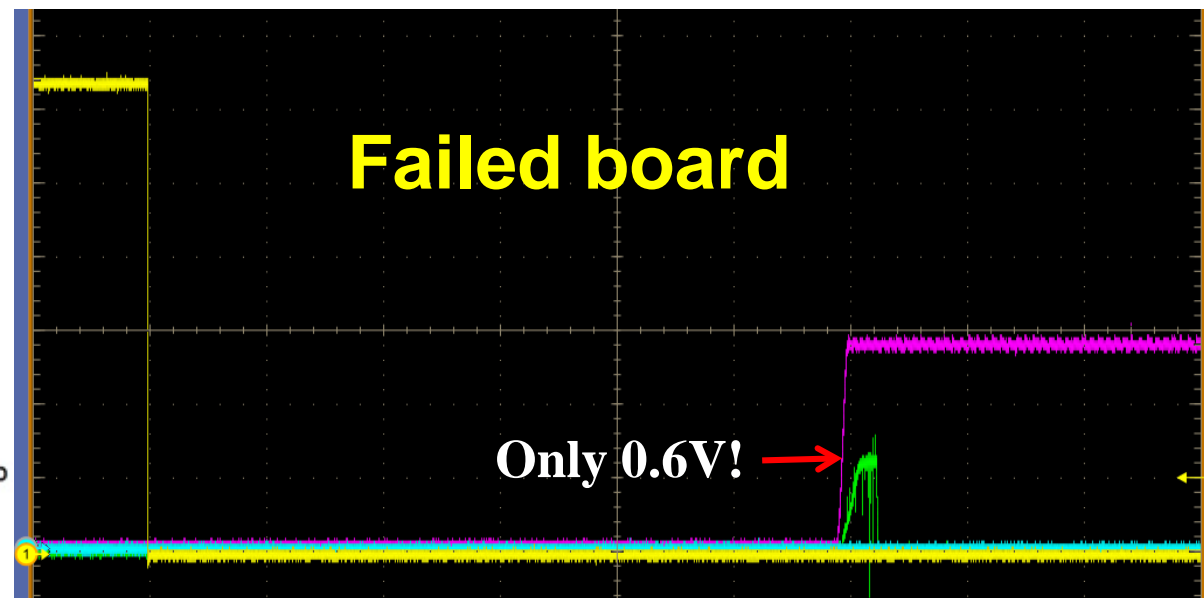
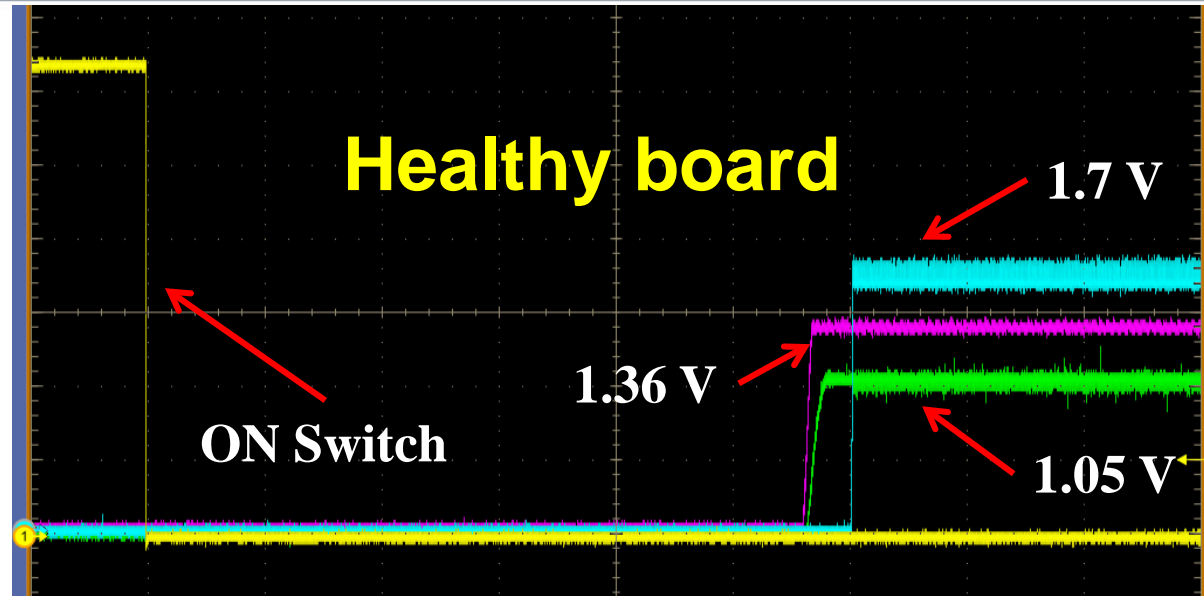
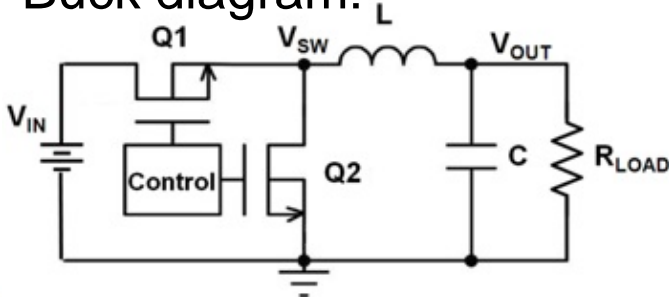
A (special) case of “hard failure”

Power supply to the CPU
(Dell laptop mother board)



Red – On all the time
Black – Start with the ON switch

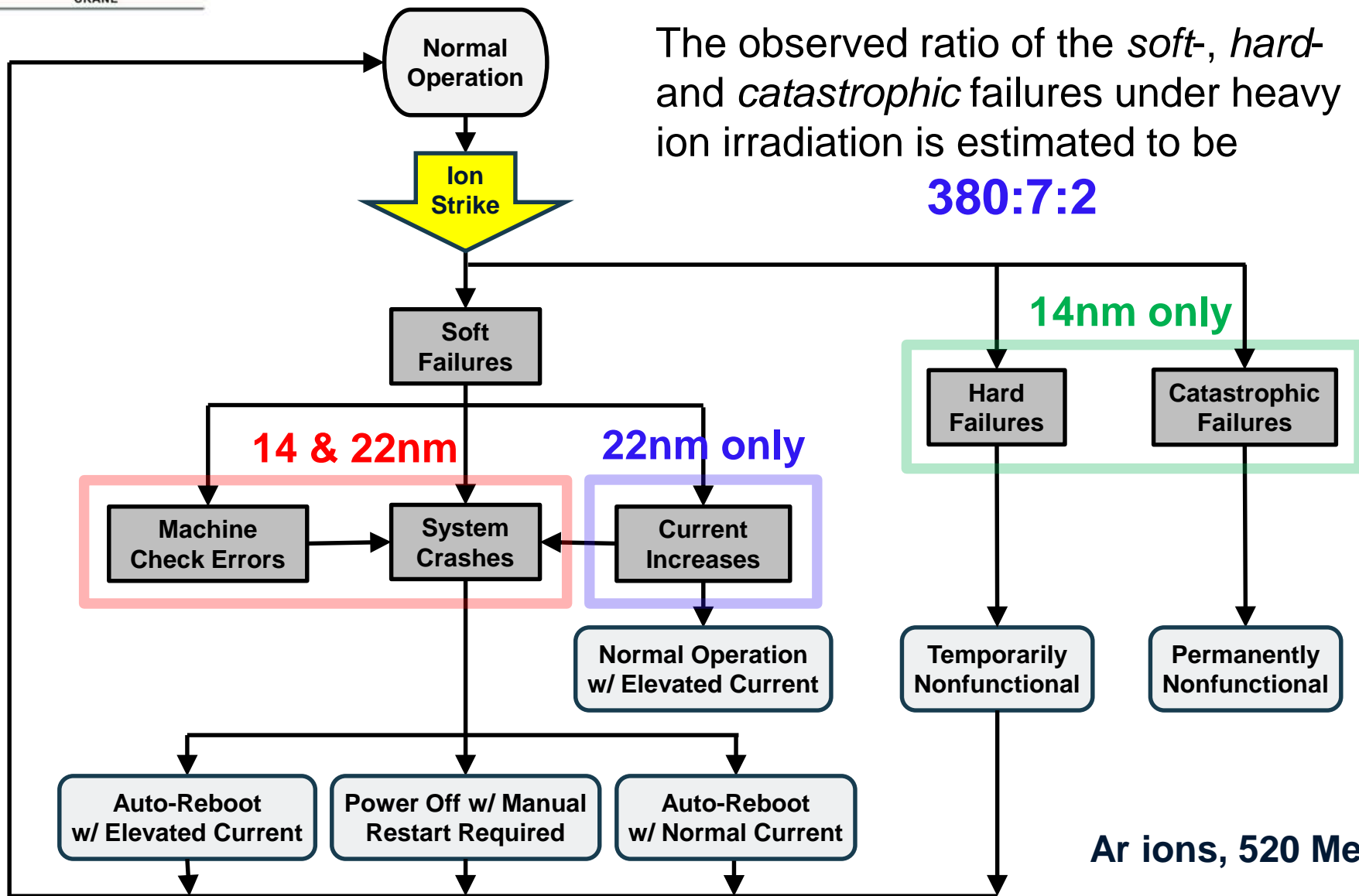
Buck diagram:



Heavy Ion Event Types (expanded)

The observed ratio of the *soft*-, *hard*- and *catastrophic* failures under heavy ion irradiation is estimated to be

380:7:2



14nm Intel Microprocessor Package

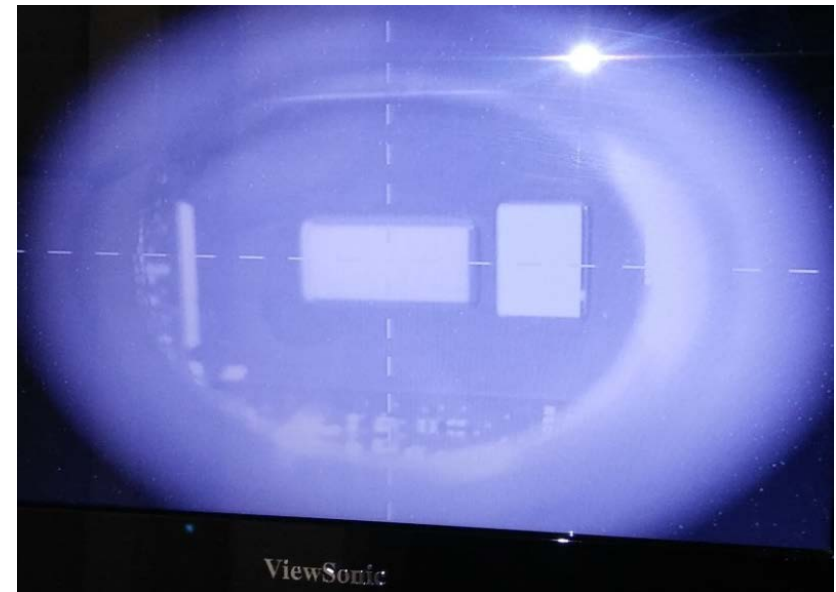
**BGA package, 2 die,
PCH = Platform Controller Hub**

32 nm planar PCH die



14 nm FinFET CPU die

TAMU beam line view



Tracing the short: CPU die

Direct short (0.2 Ω) on processor 1.05 V power pin to GND

- Neocera magnetic microscope (SQUID and GMR probes) used to identify current path on 1.05 V to GND after catastrophic failure
- Externally applied AC current of 50 mA at 5.3 kHz
- 25 to 50 μm clearance from the top surface and 15 to 50 μm lateral steps
- Two catastrophically failed boards – identical results!

No signs of a short path ...

Magnetic field mapping

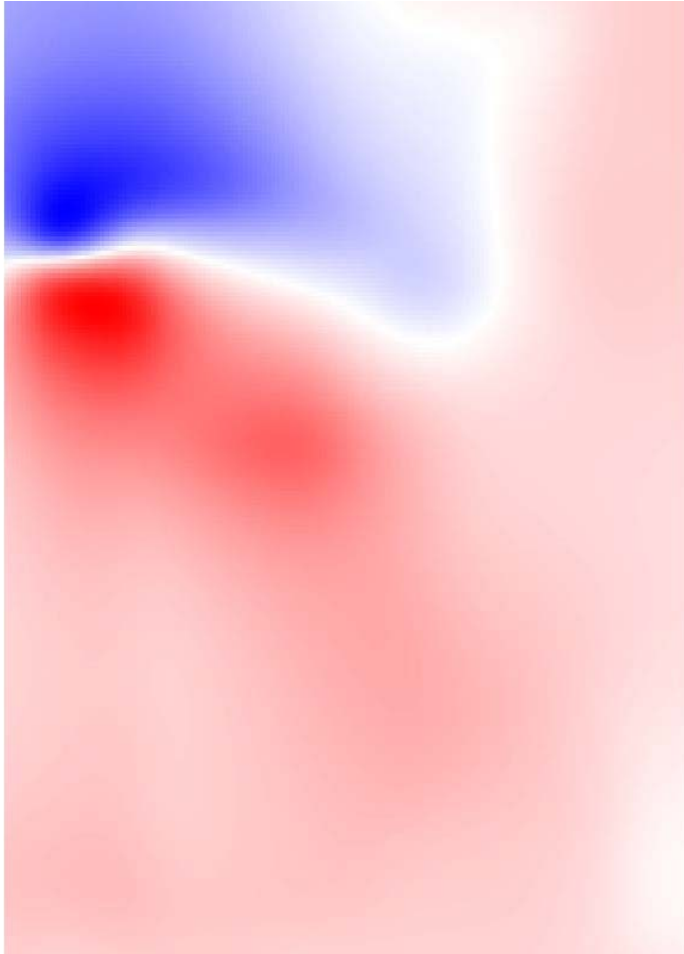


Current density mapping

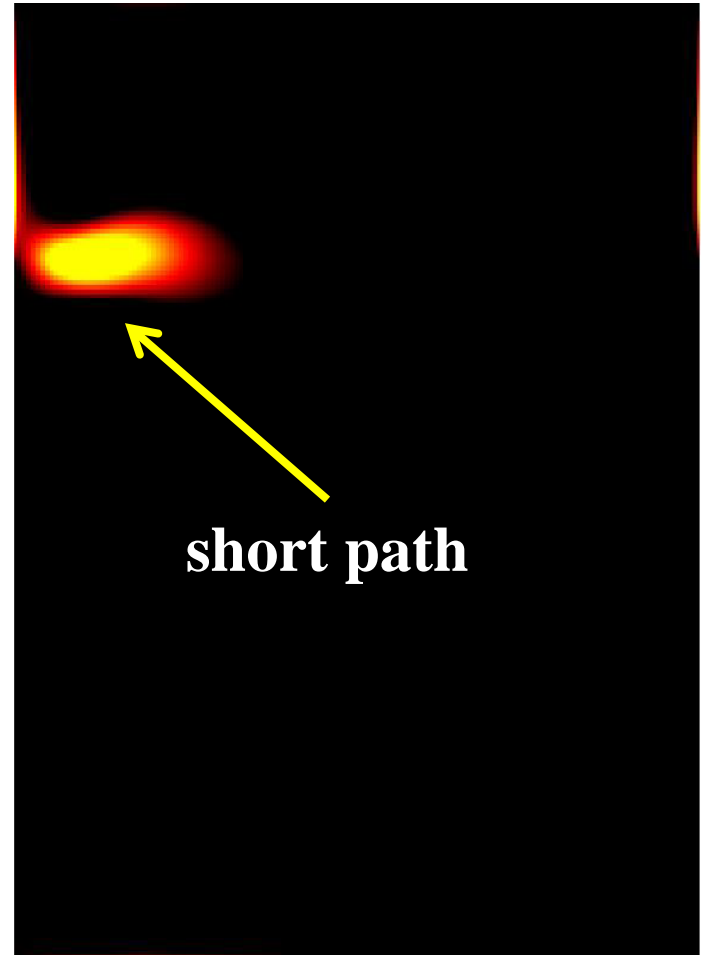


Magnetic microscope: PCH die

Magnetic field mapping



Current density mapping



Two boards – identical results!

DCG IR laser scanning microscopy

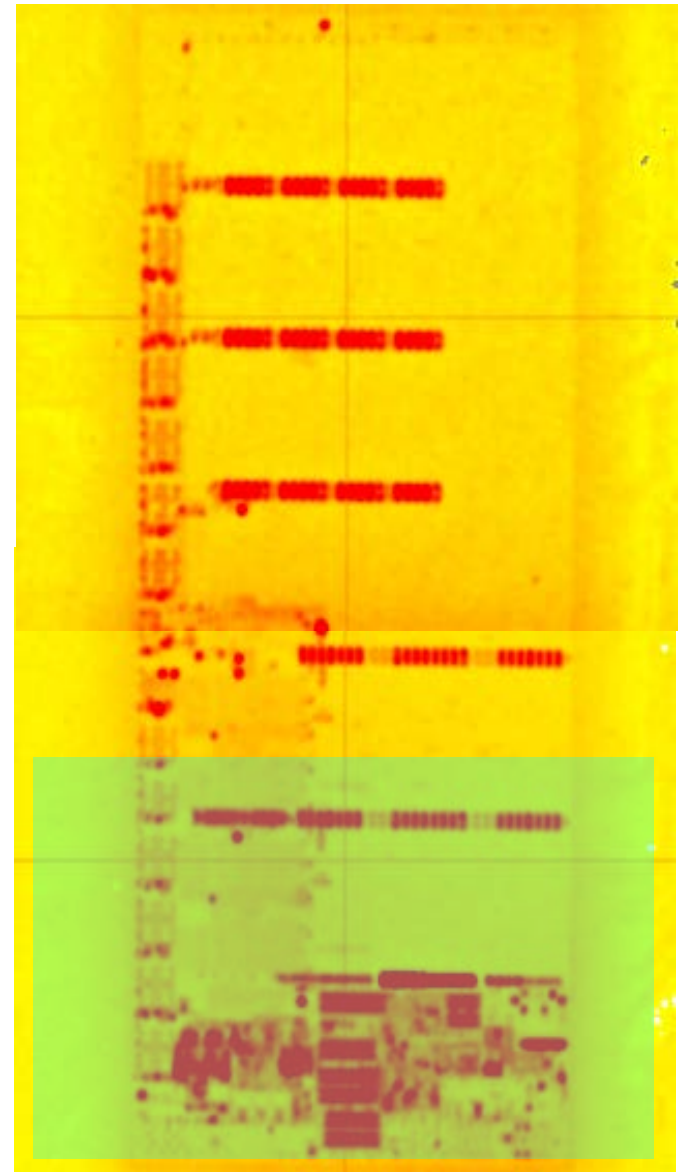
- IR photoemission (PEM) indicates high current (and high activity) areas
- Two lasers available for laser scanning (LSM):
 - 1064 nm – producing e/h pairs, similar to heavy ions
 - 1340 nm – just heat
- Rastering across the entire die or selected areas. We can control laser power and scan rate



- **Can we simulate radiation failures (soft, hard and catastrophic) using LSM technique? (cheaper than \$1000/hour heavy ion beam)**
- **The laser beam is easy to focus to a micron size spot. Can we pinpoint the sensitive area for failures?**
- **LSM irradiates one spot at a time**

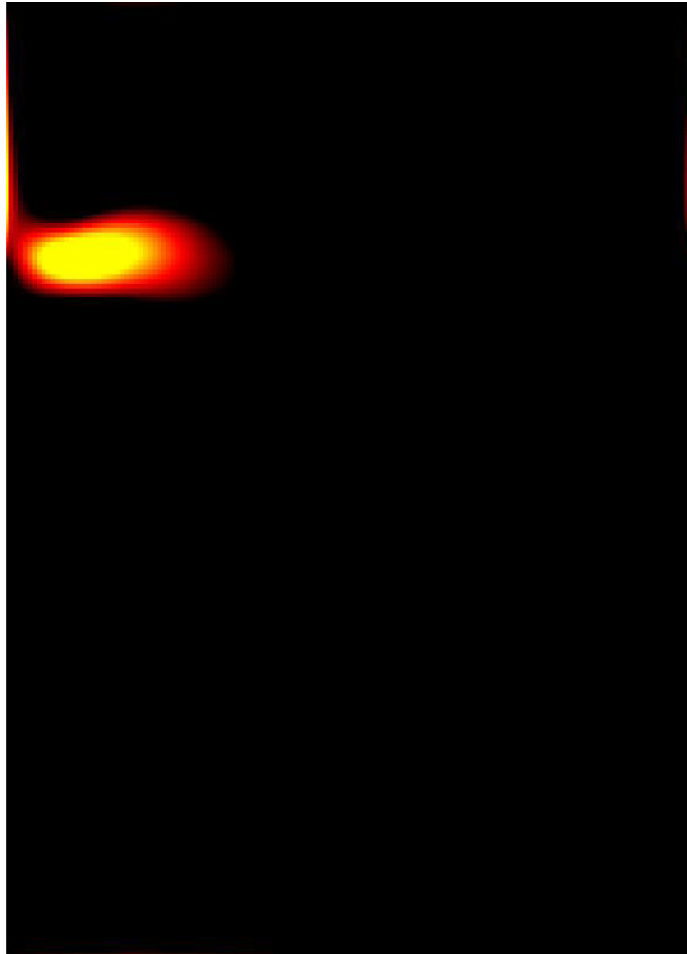
The CPU die

- 1064 nm laser causes soft failures on the CPU die at powers of 2 – 5 mW ($\times 1$ objective, scan rate 217 $\mu\text{s}/\text{pixel}$)
- The bottom 1/3 of the die is much more sensitive than the upper 2/3
- 1340 nm laser at up to 80 mW power did not cause ANY upset at multiple scans



Photoemission from the PCH die

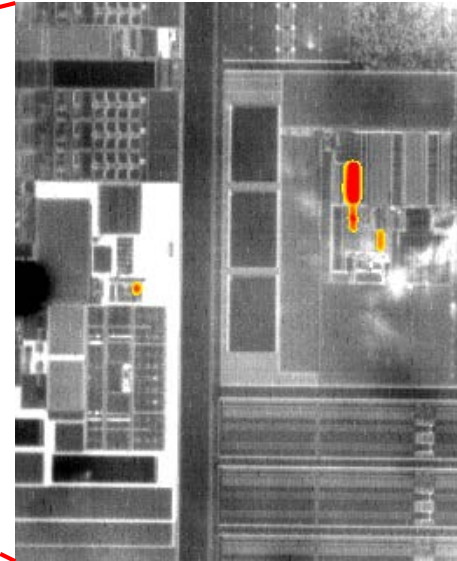
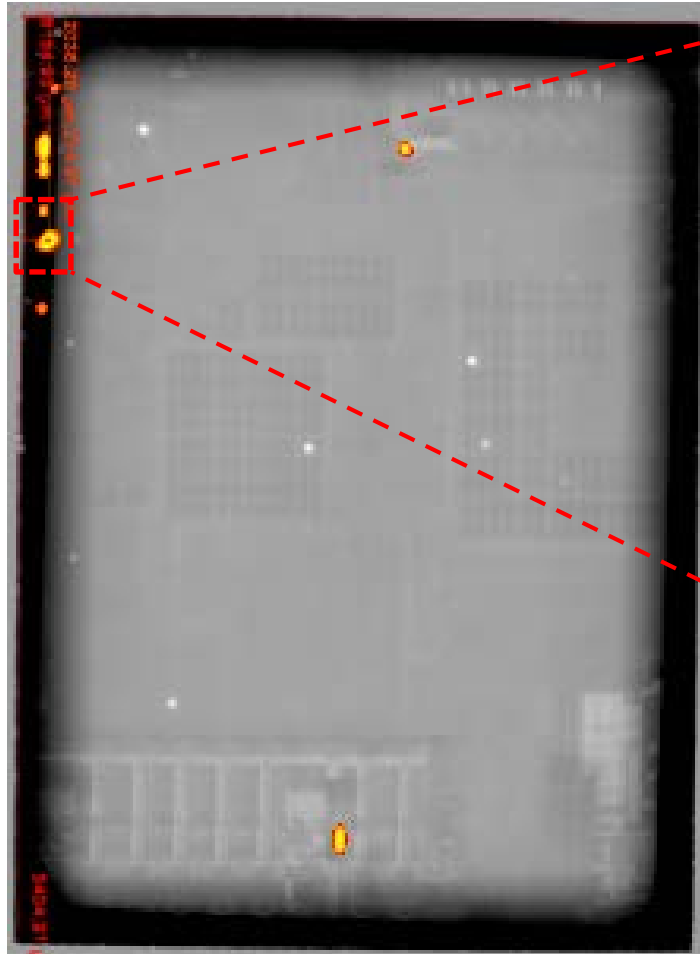
Short path
(catastrophically failed
package)



IR photoemission from a healthy package

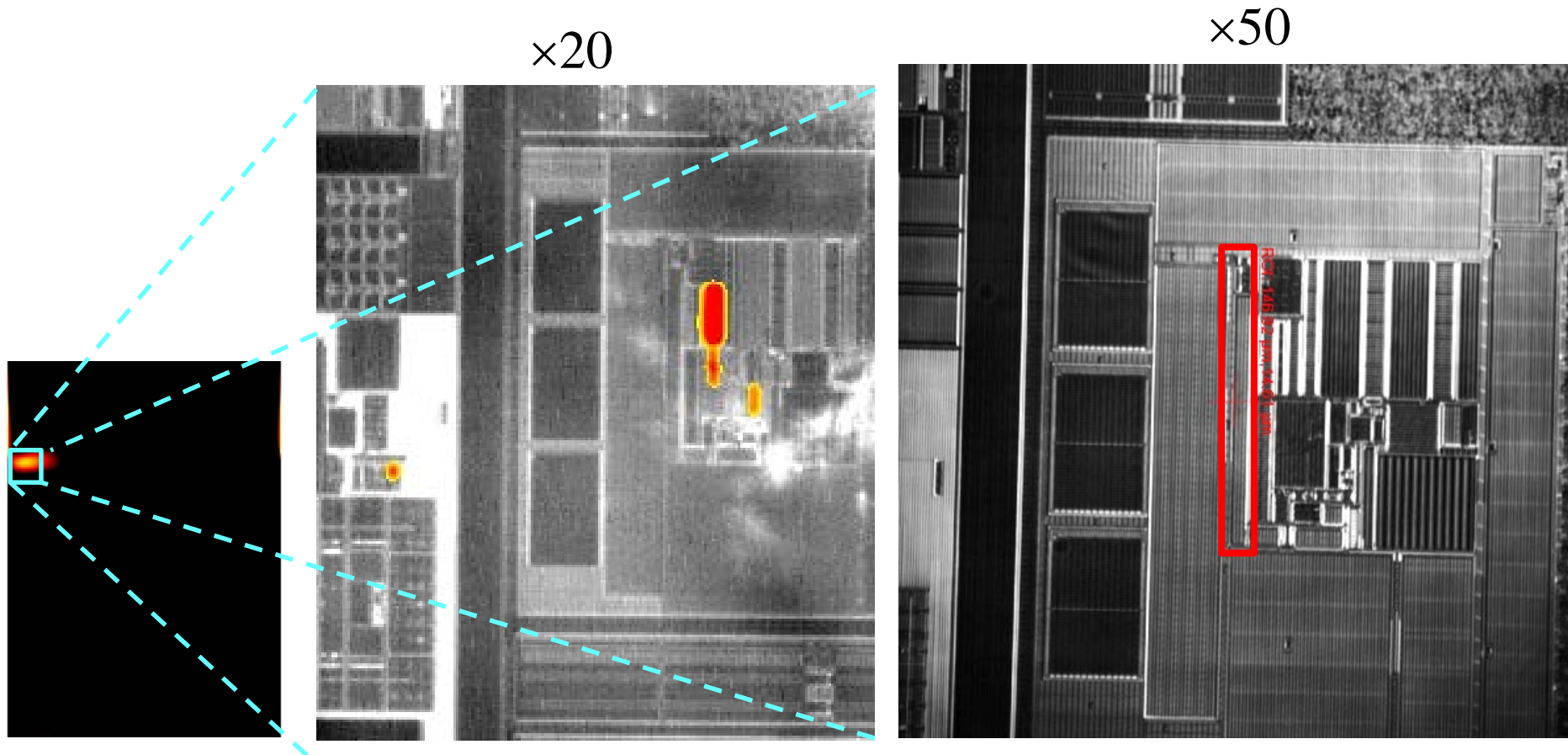
×1 Objective

×20 Objective



1064 nm laser on the PCH die

- The most sensitive area ($9\ \mu\text{m} \times 140\ \mu\text{m}$) on the PCH die occasionally causes hard failures for about 10 min at laser power of about 5 mW!
- 1340 nm laser @ up to 80 mW does not cause ANY upsets



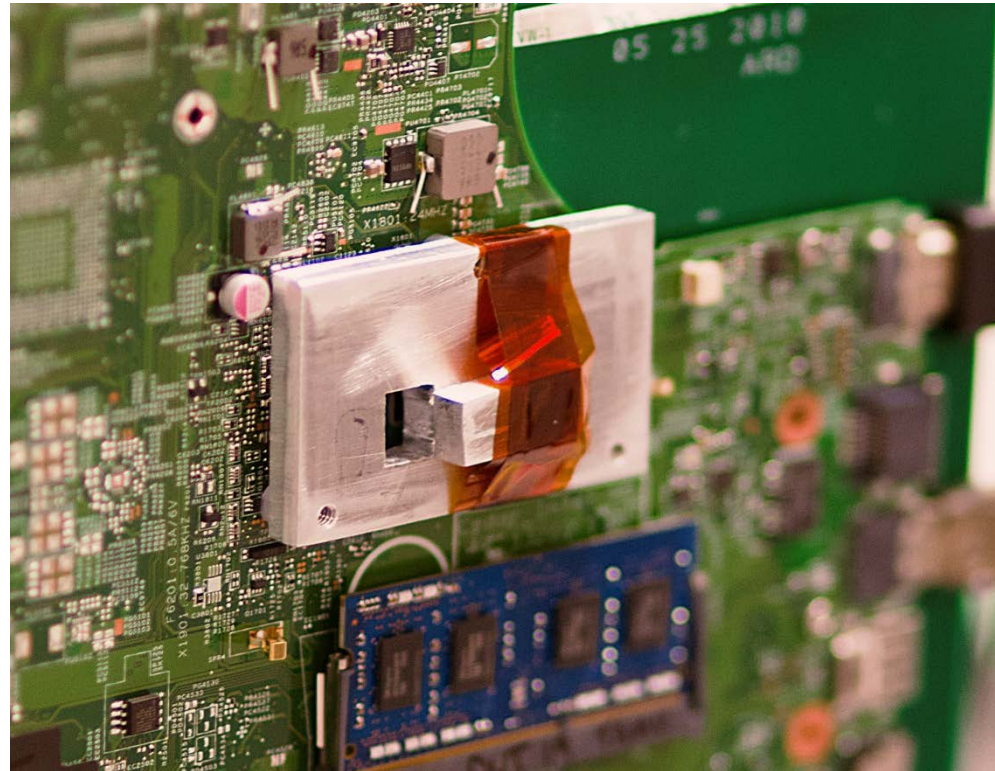
Conclusions

- **Heavy-ion-induced *hard-* and *catastrophic* failures do not appear to be related to the Intel 14nm Tri-Gate FinFET process. They originate from a small ($9\ \mu\text{m} \times 140\ \mu\text{m}$) area on the 32nm planar PCH die (not the CPU) as initially speculated**
- **The *hard failures* seem to be due to a SEE but the exact physical mechanism has yet to be identified. Some possibilities include latch-ups, charge/ion trapping or implantation, ion channels, or a combination of those (in biased conditions!)**
- **The mechanism of the *catastrophic* failures seems related to the presence of electric power (1.05V core voltage)**
- **1064 nm laser mimics ionization radiation and induces *soft-* and *hard failures* as a direct result of electron-hole pair production, not heat**
 - Cost and convenience
 - Laser can be focused within a micrometer size area to selectively study small components.
 - Necessity for thinning and polishing and other considerations
- **14nm FinFET processes continue to look promising for space radiation environments**

Recent tests (May, 2016) at TAMU

Ar ions, by A. Williams & C. Szabo:

- Two hard failures on the PCH die
- No hard failure on the CPU die



Possible future paths:

- Landscape info from Intel (?)
- Elementary mechanisms (but how?!?)
- Power consumption vs radiation dose